

# Gallium Doping of Monolayer TMDs with Density and Spatial Control

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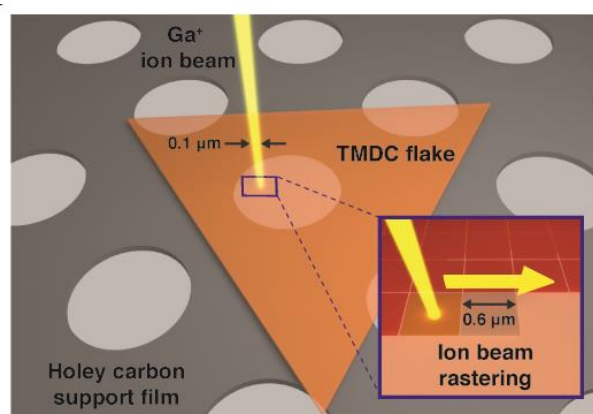
Doping offers a way of engineering two-dimensional (2D) materials for electronic, photonic, and spintronic applications. We show that 2D transition metal dichalcogenides (TMDs) can be variably doped with spatial and density control using an industry-standard 30 keV focused Ga<sup>+</sup> ion beam. Aberration-corrected scanning transmission electron microscopy (AC-STEM) and single-atom electron energy loss spectroscopy (EELS) provide direct evidence that transition metal atoms, Mo and W, are replaced with single Ga atoms up to a concentration of  $2.4 \times 10^{14}$  Ga/cm<sup>2</sup>. Photoluminescence (PL) spectroscopy and density functional theory (DFT) show that variable Ga doping densities modify the electronic structure, shift the PL peak position, and induce n-type behavior in WS<sub>2</sub>. We also show spatially-controlled doping of 2D flakes on Si/SiO<sub>2</sub> substrates. Finally, we perform simulations and atomic force microscopy to investigate potential doping mechanisms and study dynamical effects of Ga<sup>+</sup> irradiation on 2D materials. The methods presented here can be extended to other 2D materials and ion beam sources.

## References

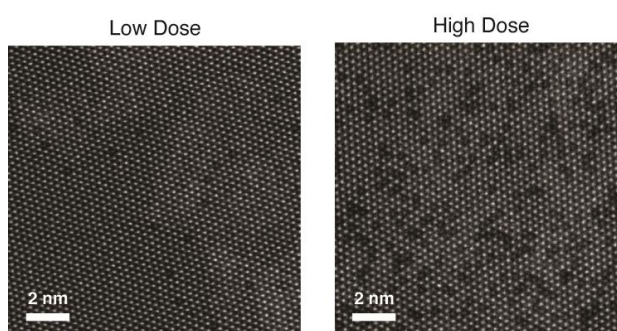
[1] P. Masih Das, J.P. Thiruraman, A. Yoshimura, G. Danda, V. Meunier, M. Drndić. In review.

[2] J.P. Thiruraman, K. Fujisawa, G. Danda, P. Masih Das, T. Zhang, A. Bolotsky, N. Perea-Lopez, A. Nicolai, P. Senet, M. Terrones, M. Drndić. *Nano Lett.* 18 (2018) 1651-1659.

## Figures



**Figure 1:** Graphic of the irradiation mechanism for monolayer TMDs (orange) suspended over 1-micron diameter holes using a focused Ga<sup>+</sup> ion beam (yellow). The inset illustrates the raster pattern of the FIB.



**Figure 2:** AC-STEM images of monolayer WS<sub>2</sub> exposed to ion beam irradiation with  $D = 5.1 \times 10^{13}$  ions/cm<sup>2</sup> and  $D = 6.3 \times 10^{14}$  ions/cm<sup>2</sup>. Due to the Z-contrast behavior of HAADF imaging, the image intensity of Ga dopants is weaker compared to heavier W atoms.